


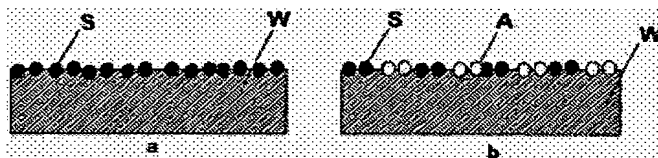


STRUCTURED SURFACES HAVING ELEVATIONS AND DEPRESSIONS, METHOD FOR PRODUCING SURFACES OF THIS TYPE AND THE USE THEREOF**Patent number:** WO03052014**Publication date:** 2003-06-26**Inventor:** KUEHNLE ADOLF [DE]; JOST CARSTEN [DE]; SCHLEICH BERNHARD [DE]; NUN EDWIN [DE]; SCHMIDT FRIEDRICH GEORG [DE]; ABBENHUIS HENDRIKUS CORNELIS L [NL]**Applicant:** CREAIVIS TECH & INNOVATION GMBH [DE]; KUEHNLE ADOLF [DE]; JOST CARSTEN [DE]; SCHLEICH BERNHARD [DE]; NUN EDWIN [DE]; SCHMIDT FRIEDRICH GEORG [DE]; ABBENHUIS HENDRIKUS CORNELIS L [NL]**Classification:****- international:** C09D183/04; C08L83/04; C08J7/04; C09D4/00; C03C17/30**- european:** C03C17/00D; C03C17/30; C09D5/00; C09D7/12M**Application number:** WO2002EP12486 20021108**Priority number(s):** DE20011060053 20011206; DE20021049453 20021024**Also published as:** DE10249453 (A1)**Cited documents:** EP0825230
 WO0110871
 US6270561**Abstract of WO03052014**

The invention relates to structured surfaces having elevations and depressions, which contain polyhedral oligomeric silicon-oxygen cluster units. Surfaces of this type can, for example, contain hydrophobic, abrasion-resistant, and scratch-resistant properties and/or self-cleaning properties. These surfaces can also be rendered non-reflective. The inventive surfaces are obtained by applying polyhedral oligomeric silicon-oxygen cluster compounds to a surface and fixing them thereon. In a particular implementation of the inventive method, the polyhedral oligomeric silicon-oxygen cluster compound, during processing, migrates to the surface and is fixed thereon.



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